

# MODIFICATION OF THE ELECTROPHYSICAL PROPERTIES OF A REAL GERMANIUM SURFACE ATTENDING THE ADSORPTION OF HYDROGEN ATOMS

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Vol. 36, No. 2, pp. 79-82, 1981

UDC 621.315.592:546.289

Adsorption of hydrogen atoms on a real surface of a germanium monocrystal vacuumed at 700°K results in a significant rise in the monotonic component of the surface recombination rate at virtually unchanged capture of charge carriers onto fast surface states. The quasicontinuous spectrum of recombination nuclei is independent of the spectrum of fast states.

Chemosorption of hydrogen atoms is frequently employed as a convenient model system in analytic studies of surface physics [1,2]. The few experiments with adsorption of hydrogen atoms were performed primarily on atomically pure Ge surfaces [2,3] and in the Ge-electrolyte system [4]. The real Ge surface, bordering on the vacuum, has been least explored in this respect.

We employed a combined experimental field-effect facility [5] for measuring the modification of the surface potential  $Y_s$ , capture onto fast surface states  $Q_{fs}$  and rates of surface recombination  $S$  on a real (111) Ge surface following adsorption of hydrogen atoms. The n-Ge monocrystals ( $\rho = 30-35$  ohm·cm) were etched in a standard peroxide etching agent and then dehydrated for 5 min in oil-free vacuum of approximately  $10^{-8}$  mm Hg at  $T_B = 500^\circ\text{K}$  (Ge-500) and  $700^\circ\text{K}$  (Ge-700). The molecular hydrogen was fed to the vacuum system through a zeolite trap and a palladium capillary. Atomic hydrogen was obtained by hydrolyzing  $\text{H}_2$  on a hot tungsten wire and in a high frequency discharge.

Unlike the study by Neizvestnyi with his coworkers [6], adsorption of molecular hydrogen did not modify the electrophysical properties of the surfaces of Ge-500 and Ge-700 specimens. The latter is confirmed by data of Kompaniets [7], according to which the adhesion factor of  $\text{H}_2$  is less than  $10^{-8}$ . Adsorption of hydrogen atoms on the Ge-500 specimen shifted  $Y_{s0}$  by 1.5-2 kT/q in the direction of positive values and virtually had no effect on  $S$  and  $Q_{fs}$  (Fig. 1). After heating of specimens at 700°K in accordance with the technique of Novototskii-Vlasov [5], only the monotonic component of the surface recombination rate  $S_m$  was observed (Fig. 2). Adsorption of atomic hydrogen resulted in shifting  $Y_{s0}$  by 1.5-3 kT/q into the positive region (see the arrows in Fig. 2), which does not contradict the results of Surnev and Bliznakov [3]. Simultaneously with the change in  $Y_{s0}$ , and with approximately the same kinetics the value of  $S_m$  increased, as can

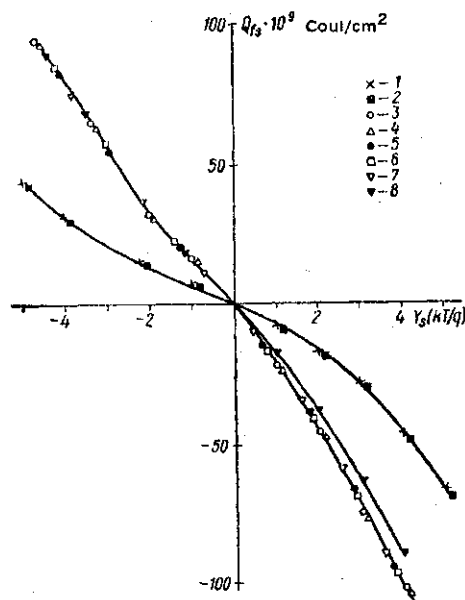


Fig. 1

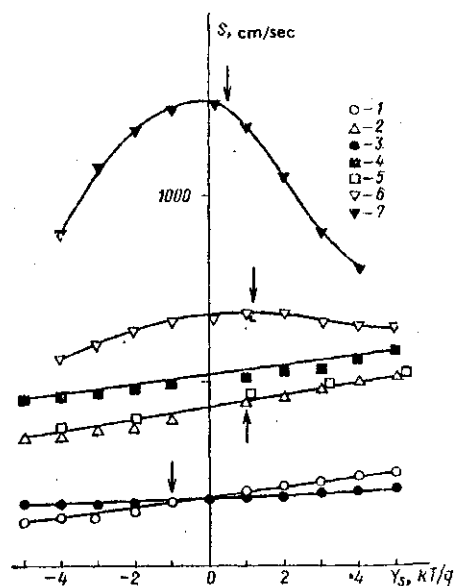


Fig. 2

Fig. 1. Curves of capture onto fast surface states: 1) Ge-500 specimens; 2) after adsorption of atomic hydrogen on Ge-500 specimens; 3) Ge-700 specimens; 4) after adsorption of atomic hydrogen on Ge-700 specimens; 5) after heating of Ge(H) specimens at 600°K; 6) after adsorption of pyridine on Ge(H) specimens; 7) after adsorption of H<sub>2</sub>O on Ge(H) specimens; 8) after heating of Ge(H) specimens in O<sub>2</sub>.

Fig. 2. Curve of the surface recombination rate vs.  $Y_s$ : 1) Ge-700 specimens; 2) after adsorption of atomic hydrogen on Ge-700 specimens; 3) after heating of Ge(H) specimens at 600°K; 4) after adsorption of atomic hydrogen on Ge-700 upon supply of negative (with respect to Ge) potential to the grid; 5) after adsorption of pyridine on a Ge(H) specimen; 6) after adsorption of H<sub>2</sub>O on a Ge(H) specimens; 7) after heating of Ge(H) specimens in O<sub>2</sub>.

be seen in Fig. 2. The steady state values of  $Y_{s0}$  and  $S_m$  were attained after holding the specimen for 40 min in an atmosphere of hydrogen atoms. Curves of capture onto the fast states virtually did not change after adsorption of atomic hydrogen (see Fig. 1). The evacuation of the specimen, which was performed at 300°K after adsorption virtually did not change  $Y_{s0}$ ,  $Q_{fs}$  and  $S_m$ . However, when  $T_B$  was raised to 600°K the above parameters took on values close to starting values (with respect to adsorption), which is in agreement with data on desorption of hydrogen [7]. Adsorption of atomic hydrogen, obtained both by pyrolysis and in the high frequency discharge, resulted in the same changes in  $Y_{s0}$ ,  $Q_{fs}$  and  $S_m$ . To establish the existence of adsorption of charged particles (H<sup>+</sup>) a grid, charged with respect to Ge, was placed between the specimen and the source. The application to the grid of potentials of different signs virtually did not change  $S_m$  - see Fig. 2. The presence of H<sup>+</sup> on the surface is also contraindicated by data on adsorption of proton-acceptor pyridine molecules (PyH<sup>+</sup> complexes). Adsorption of Py had no effect on  $Q_{fs}$  and  $S_m$  (see Figs. 1 and 2).

The significant change in  $S_m$  upon adsorption of atomic hydrogen is an additional confirmation of the data of Neizvestnyi et al. [8], who showed that this component of the surface recombination rate is not related to recombination in the region of the space charge. The steep rise in  $S_m$  at constant  $Q_{fs}$  apparently points to the fact that the system of nuclei responsible for recombination is independent of the system of fast states. Most probably chemisorption of atomic hydrogen is accompanied by breaking of Ge-Ge or Ge-O-Ge bonds on the Ge-GeO<sub>2</sub> boundary and restructuring of the boundary layer structure. This involves formation of the GeH hydride groups, which is confirmed by IR spectra [9]. In the case of atomically pure surface of Ge the reconstruction of the surface and formation of GeH groups are indicated by data of diffraction of slow electrons and of UV spectroscopy [2]. Hydrogen atoms at such surfaces interact with free Ge radicals [1], and then the surface acquires a negative charge [3]. In the case of Ge-700 specimens the interaction of hydrogen atoms with chemically saturated bonds results in formation of GeH and GeOH groups, with positive charging of the surface. The Ge-vacuum interface differs from that of Ge-electrolyte. In the presence of an electrolyte the adsorption of hydrogen was accompanied by cymbate growth of the bell-shaped component of the surface recombination rate and of  $Q_{fs}$  [4].

Holding a specimen with hydrated surface (Ge(H)) in water vapor ( $p = 8$  mm Hg) for 2 hr resulted in some distortion of linearity of  $S_m(Y_s)$ ; the bell-shaped component manifested itself more clearly after heating the Ge(H) specimen in dry oxygen at 400°K - see Fig. 2. Note that H<sub>2</sub>O was found to precipitate in spectra of thermodesorption from the Ge(H) specimens, following adsorption of O<sub>2</sub> [7]. Adsorption of O<sub>2</sub> and H<sub>2</sub>O involves partial breakup of GeH groups and additional oxidation of the Ge surface. These processes result in restructuring of the subsurface region of the semiconductor so that a part of states may drop out from the quasicontinuous spectrum of recombination levels. The latter, according to the model of Neizvestnyi and Ovsyuk [10], will result in appearance of the bell-shaped component of the surface recombination rate.

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14 May 1980

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